502648826 01/24/2014

PATENT ASSIGNMENT COVER SHEET

Electronic Version v1.1 Stylesheet Version v1.2

EPAS ID: PAT2695434

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	ASSIGNMENT

CONVEYING PARTY DATA

Name	Execution Date
En-Chiuan Liou	10/25/2013
Sho-Shen Lee	10/24/2013
Wen-Liang Huang	10/24/2013
Chang-Mao Wang	10/24/2013
Kai-Lin Chuang	10/24/2013

RECEIVING PARTY DATA

Name:	UNITED MICROELECTRONICS CORP.
Street Address:	No.3, Li-Hsin Road 2, Science-Based Industrial Park
City:	Hsin-Chu City
State/Country:	TAIWAN

PROPERTY NUMBERS Total: 1

Property Type	Number
Application Number:	14067986

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ATTORNEY DOCKET NUMBER:	NAUP1994USA
NAME OF SUBMITTER:	KATE YEH
Signature:	/KATE YEH/
	PATENT

502648826 REEL: 032034 FRAME: 0144

Date:	01/24/2014
Total Attachments: 10	
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Title of Invention: PHOTOMASK AND FABRICATION METHOD THEREOF

As the below named inventor, I here This declaration is directed to:	eby declare that:			
The attached application, or	r			
☐ United States application no	umber	file	d on	, or
☐ PCT international application	on number		filed on	
The above-identified application was	s made or authorized t	o be made by m	ie.	
I believe that I am the original inventapplication	tor or an original joint i	nventor of a clai	med invention in	n the
I hereby acknowledge that any willfu under18 U.S.C. 1001 by fine or impr	ul false statement mad risonment of not more	e in this declara than five (5) yea	tion is punishab ars, or both.	le
In consideration of the payment by	UNITED MICROE CORP.	LECTRONICS	having a po	ostal address of
No.3, Li-Hsin Road 2, Science	e-Based Industrial	Park, Hsin-C	hu City 300,	Taiwan, R.O.C.
(referred to as "ASSIGNEE"below) t acknowledged, andfor other good ar	o I of the sum of One I nd valuable considerat	Dollar (\$ 1.00), t ion.	he receipt of wh	ich is hereby
I hereby sell, assign and transfer to the entire right, title and interest in a invention as above-identified application of the above application of substitutes, or extensions thereof, and	ind to any and all impro ation and, in and to, all or any continuations, co	ovements which Letters Patent to Intinuation-in-pa	are disclosed in to be obtained for trt, divisions, rer	n the or said newals,
I hereby covenant that no assignme entered into which would conflict wit	nt, sale, agreement or th this assignment;	encumbrance h	as been or will l	be made or
I further covenant that ASSIGNEE wand documents relating to said invertence known and accessible to I and will to related thereto and will promptly exe	ntion and said Letters estify as to the same ir	Patent and legal any interference	l equivalents as e, litigation prod	may be
representatives any and all papers, maintain, issue and enforce said app equivalents thereof which may be no IN WINTNESS WHEREOF, I have h	plication, said inventio ecessary or desirable t	n and said Lette o carry out the p	rs Patent and sa proposes thereo	
Note: An application data sheet (PTo				

Page 1 of 10

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266

LEGAL NAME OF INVENTOR(ASSIGNOR)

Inventor:

En-Chiuan Liou

2013. (0.25

En Chivan Lou

NPO#NAU-P1994-USA:0

CUST#UMCD-2013-0266

Page

F#NPO-P0002E-US1201 DSC0-102U009210

Title of Invention:			
PHOTOMASK AND	FABRICATION	METHOD	THEREOF

As the below named inventor, I here This declaration is directed to:	by declare that:		
☑ The attached application, or	•		
☐ United States application nu	ımber	filed on	, or
☐ PCT international applicatio	n number	filed on	
The above-identified application was	made or authorized to be made l	by me.	
I believe that I am the original invent application.	or or an original joint inventor of a	claimed invention in the	
I hereby acknowledge that any willfu under18 U.S.C. 1001 by fine or impr	I false statement made in this dec isonment of not more than five (5)	laration is punishable years, or both	
In consideration of the payment by	UNITED MICROELECTRON CORP.	IICS having a postal add	lress of
No.3, Li-Hsin Road 2, Science	-Based Industrial Park, Hsi	n-Chu City 300, Taiwan	, R.O.C.
(referred to as "ASSIGNEE"below) to acknowledged, andfor other good ar	o I of the sum of One Dollar (\$ 1.0 ad valuable consideration.	0), the receipt of which is he	reby
I hereby sell, assign and transfer to a the entire right, title and interest in a invention as above-identified applica invention by the above application of substitutes, or extensions thereof, ar	nd to any and all improvements w tion and, in and to, all Letters Pate rany continuations, continuation-i	hich are disclosed in the ent to be obtained for said n-part, divisions, renewals,	EE
I hereby covenant that no assignment entered into which would conflict with	nt, sale, agreement or encumbran n this assignment;	ce has been or will be made	or
I further covenant that ASSIGNEE w and documents relating to said inver known and accessible to I and will te related thereto and will promptly exe	ntion and said Letters Patent and I estify as to the same in any interfe	egal equivalents as may be rence, litigation proceeding	ts
representatives any and all papers, i maintain, issue and enforce said app equivalents thereof which may be ne IN WINTNESS WHEREOF, I have h	blication, said invention and said L ecessary or desirable to carry out t	etters Patent and said the proposes thereof.	of signing)
Note: An application data sheet (PTC inventive entity, must accompany thi	D/SB/14 or equivalent), including r s form. Use this form for <u>each add</u>	naming the entire litional inventor.	

Page 3 of 10

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266

LEGAL NAME OF INVENTOR(ASSIGNOR)

Inventor: Sho-Shen Lee

Date:

OCT 24 2013

Signature:

Sho Shen Laa

Page 4 of 10

F#NPO-P0002E-US1201 DSC0-102U009210

Title of Invention: PHOTOMASK AND FABRICATION METHOD THEREOF

As the below named inventor, I here This declaration is directed to:	by declare that:		
☑ The attached application, or			
☐ United States application number		filed on	, or
☐ PCT international applicatio	n number	filed on	
The above-identified application was	made or authorized to be made	by me.	
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(referred to as "ASSIGNEE"below) to acknowledged, andfor other good an	o I of the sum of One Dollar (\$ 1. Id valuable consideration.	00), the receipt of which is he	reby
I hereby sell, assign and transfer to A the entire right, title and interest in ar invention as above-identified applica invention by the above application or substitutes, or extensions thereof, ar	nd to any and all improvements wation and, in and to, all Letters Par any continuations, continuation	which are disclosed in the tent to be obtained for said -in-part, divisions, renewals,	EE
I hereby covenant that no assignment entered into which would conflict with		nce has been or will be made	or
I further covenant that ASSIGNEE w and documents relating to said inver known and accessible to I and will te related thereto and will promptly exe	ntion and said Letters Patent and estify as to the same in any interf	l legal equivalents as may be erence, litigation proceeding	ts
representatives any and all papers, i maintain, issue and enforce said app equivalents thereof which may be ne IN WINTNESS WHEREOF, I have h	olication, said invention and said ecessary or desirable to carry out	Letters Patent and said the proposes thereof.	of signing)
Note: An application data sheet (PTC inventive entity, must accompany thi			

Page 5 of 10

LEGAL NAME OF INVENTOR(ASSIGNOR)

Inventor: Wen-Liang Huang

Date:

OCT 24 2013

Signature:

Wen Euorg Huang

Page 6 of 1

F#NPO-P0002E-US1201 DSC0-102U009210

Title of Invention: PHOTOMASK AND FABRICATION METHOD THEREOF

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☑ The attached application, or	7			
☐ United States application nu	ımber	filed	l on	, or
☐ PCT international applicatio	n number	fi	led on	_
The above-identified application was	made or authorized to	be made by me	?.	
I believe that I am the original invent application.	or or an original joint in	ventor of a claim	ned invention in the	
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I hereby sell, assign and transfer to a the entire right, title and interest in a invention as above-identified applica invention by the above application of substitutes, or extensions thereof, ar	nd to any and all improvition and, in and to, all I r any continuations, cor	vements which a letters Patent to ntinuation-in-part	are disclosed in the be obtained for said t, divisions, renewals,	
I hereby covenant that no assignment entered into which would conflict with	nt, sale, agreement or en this assignment;	encumbrance ha	s been or will be made	e or
I further covenant that ASSIGNEE w and documents relating to said inver known and accessible to I and will to related thereto and will promptly exe	ntion and said Letters P estify as to the same in	atent and legal any interference	equivalents as may be , litigation proceeding	cts
representatives any and all papers, i maintain, issue and enforce said app equivalents thereof which may be no IN WINTNESS WHEREOF, I have h	olication, said invention ecessary or desirable to	and said Letters carry out the pr	Patent and said oposes thereof.	of signing)
Note: An application data sheet (PTG inventive entity, must accompany thi				

Page 7 of 10

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266

LEGAL NA					
Inventor:	Chang-Mao Wang	•	Date:	OCT 24 2013	
Signature:	Chang. Mao Wang		_		

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266 Page 8 of 10

F#NPO-P0002E-US1201 DSC0-102U009210

Title of Invention: PHOTOMASK AND FABRICATION METHOD THEREOF

As the below named inventor, I here This declaration is directed to:	eby declare that:		
☑ The attached application, o	r		
☐ United States application no	filed on	, or	
☐ PCT international application	n number	filed on	i
The above-identified application was	s made or authorized to b	e made by me.	
I believe that I am the original inventapplication.	tor or an original joint inve	ntor of a claimed inv	ention in the
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(referred to as "ASSIGNEE"below) t acknowledged, andfor other good ar			pt of which is hereby
I hereby sell, assign and transfer to the entire right, title and interest in a invention as above-identified applica- invention by the above application o substitutes, or extensions thereof, an	nd to any and all improve ation and, in and to, all Lei r any continuations, conti	ments which are disc tters Patent to be obt nuation-in-part, divisi	closed in the ained for said ons, renewals,
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I further covenant that ASSIGNEE wand documents relating to said inver known and accessible to I and will to related thereto and will promptly exe	ntion and said Letters Pat estify as to the same in an	ent and legal equival y interference, litigati	ents as may be
representatives any and all papers, maintain, issue and enforce said app equivalents thereof which may be no IN WINTNESS WHEREOF, I have h	plication, said invention ar ecessary or desirable to c	nd said Letters Paten arry out the proposes	t and said s thereof.
Note: An application data sheet (PTo inventive entity, must accompany thi			

Page 9 of 10

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266

LEGAL NAME OF INVENTOR(ASSIGNOR)								
Inventor:	Kai-Lin Chuang	. , , ,	Date:	OCT 24 2013				
Signature:	Kai-Lin	Chuang	**************************************					

NPO#NAU-P1994-USA:0 CUST#UMCD-2013-0266 Page 10 of 10

F#NPO-P0002E-US1201 DSC0-102U009210

PATENT REEL: 032034 FRAME: 0155

RECORDED: 01/24/2014